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Claims:

1. A master mold comprising a support layer comprised of a high grinding speed material and a fine structure pattern comprised of a low grinding speed material supported by said support layer.

- 2. The master mold of claim 1, wherein said high grinding speed material is a metal material.
- 3. The master mold of claim 1 or 2, wherein low grinding speed material is glass or ceramics.
 - 4. The master mold of any of claims 1-3 wherein the mold is suitable for making plasma display panel ribs.

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- 5. The master mold of claims 1-3 wherein the mold is suitable for making microfluidic articles.
- 6. The master mold of claim 1 wherein said fine structure pattern is a grid-like protrusion pattern comprising a plurality of ridge-like protrusions arranged substantially parallel while intersecting one another with predetermined gaps among them.
 - 7. A master mold comprising:
 - a support layer comprised of a metal material;
- a fine structure pattern comprised of a glass or ceramic material formed on said support layer; wherein said fine structure pattern comprises ribs having;
 - a rib height of 150 to 300 μm,
 - a rib pitch of 150 to 800 µm, and
 - a rib width of 50 to 80 μ m.

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8. A master mold comprising a support layer comprised of a high grinding speed material and a fine structure pattern comprised of a low grinding speed material supported by said

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support layer, wherein said fine structure pattern is formed by selectively removing said low grinding speed material such that a fine structure pattern is formed.

- 9. The master mold of claim 8 wherein the low grinding material is removed by sand blasting.
 - 10. The master mold of claim 8 wherein the low grinding material is removed by chemical etching.
- 11. A method of producing a master mold comprising the steps of:

 forming a support layer from a low grinding speed material material;

 depositing a layer of a high grinding speed material on said support layer to form a

 composite material layer;

forming a mask on said composite material layer;

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- selectively removing said layer of high grinding speed material such that the support layer is exposed; and
 - peeling said mask from said layer of said high grinding speed material.
- 12. The method of claim 11, wherein said high grinding speed material is a metal material.
 - 13. The method of claim 11 or 12, wherein low grinding speed material is glass or ceramics.
- 25 14. The method of any of claims 11 to 13 wherein the high grinding speed material is removed by sand blasting.
 - 15. The method of any of claims 11 to 13 wherein the high grinding speed material is removed by chemical etching.
 - 16. The method of any of claims 11 to 15, wherein the high grinding speed material is formed by spraying, enameling or a sol-gel method.

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17. The method of any of claims 11 to 16, wherein said mask is formed by the steps of forming a layer of a mask-forming material on said composite material layer and then patterning it into a desired shape by photolithography.

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